

Docket No.: 2000P1907

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : VIRINDER GREWAL ET AL.
Filed : Concurrently herewith
Title : GATE ETCH PROCESS FOR 12 INCH WAFERS

INFORMATION DISCLOSURE STATEMENT

Hon. Commissioner of Patents and Trademarks,
Washington, D.C. 20231

Sir:

In accordance with 37 C.F.R. 1.98 copies of the following patents and/or publications are submitted herewith:

U.S. Patent No. 5,948,703 (Shen et al.) dated September 7, 1999;

U.S. Patent No. 5,874,363 (Hoh et al.) dated February 23, 1999;

U.S. Patent No. 5,843,239 (Shrotriya) dated December 1, 1998;

U.S. Patent No. 5,583,737 (Collins et al.) dated December 10, 1996;

U.S. Patent No. 5,158,644 (Cheung et al.) dated October 27, 1992;

U.S. Patent No. 5,591,301 (Grewal) dated January 7, 1997;

U.S. Patent No. 5,529,197 (Grewal) dated June 25, 1996;

Published European Patent Application No. 0 814 501 A3 (Tsal) dated December 29, 1997;

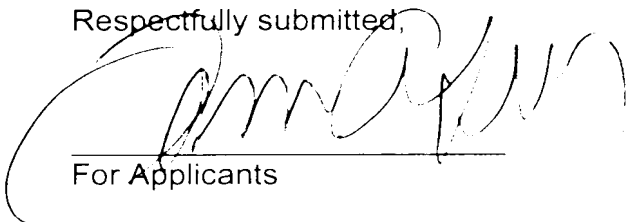
Published European Patent Application No. 0 746 015 A2 (Lee et al.) dated
December 4, 1996;

Published European Patent Application No. 0 718 868 A2 (Grewal) dated June 26,
1996;

Japanese Patent Abstracts 09045671 A (Yamazaki Shunpei) dated February 14,
1997 and

"Challenges for 300 mm Plasma Etch System Development", Sanjay Tandon, XP-
000974462, March 1998, Semiconductor International, pp. 75-82.

Respectfully submitted,



For Applicants

Date: January 16, 2002

Lerner and Greenberg, P.A.
Post Office Box 2480
Hollywood, FL 33022-2480
Tel: (954) 925-1100
Fax: (954) 925-1101

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FORM PTO-1449 (SUBSTITUTE)	Attorney Docket No.: 2000P1907
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	Applicant VIRINDER GREWAL ET AL.
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b))	Filing Date January 16, 2002

EXAMINER INITIALS		PATENT NO.	DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE
	A	5,948,703	09/99	Shen et al.			
	B	5,874,363	02/99	Hoh et al.			
	C	5,843,239	12/98	Shrotriya			
	D	5,583,737	12/96	Collins et al.			
	E	5,158,644	10/92	Cheung et al.			
	F	5,591,301	01/97	Grewal			
	G	5,529,197	06/96	Grewal			
	H						
	I						

FOREIGN PATENT DOCUMENT

		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUB CLASS	TRANSL. YES NO
	J	0 814 501 A3	12/97	Europe			X
	K	0 746 015 A2	12/96	Europe			X
	L	0 718 868 A2	06/96	Europe			X
	M						
	N						

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

	Japanese Patent Abstracts 09045671 A (Yamazaki Shunpei) dated February 14, 1997
	"Challenges for 300 mm Plasma Etch System Development", Sanjay Tandon, XP-000974462, March 1998, Semiconductor International, pp. 75-82
EXAMINER	DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.